

First principles study of $\text{BA}/\text{MoSi}_2\text{N}_4$ van der Waals heterostructure: tunable electronic and optical properties via vertical strain

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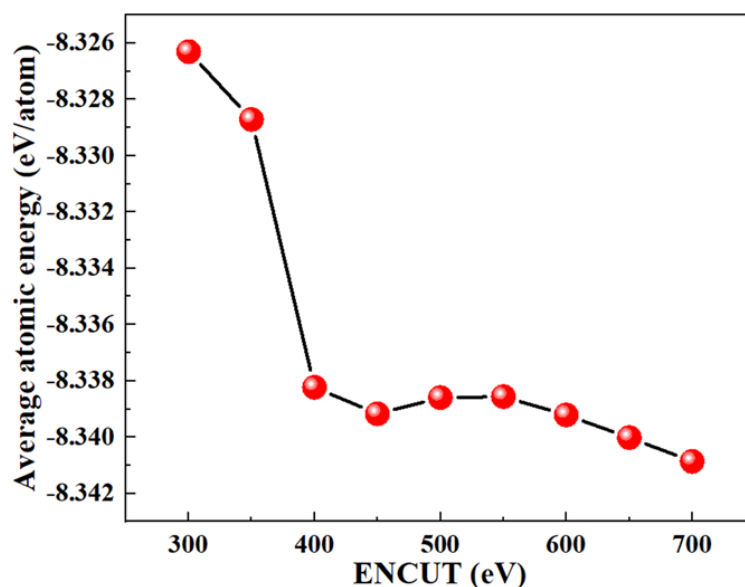


Fig. S1 Convergence test of $\text{BA}/\text{MoSi}_2\text{N}_4$ heterostructure under different cut-off energies.

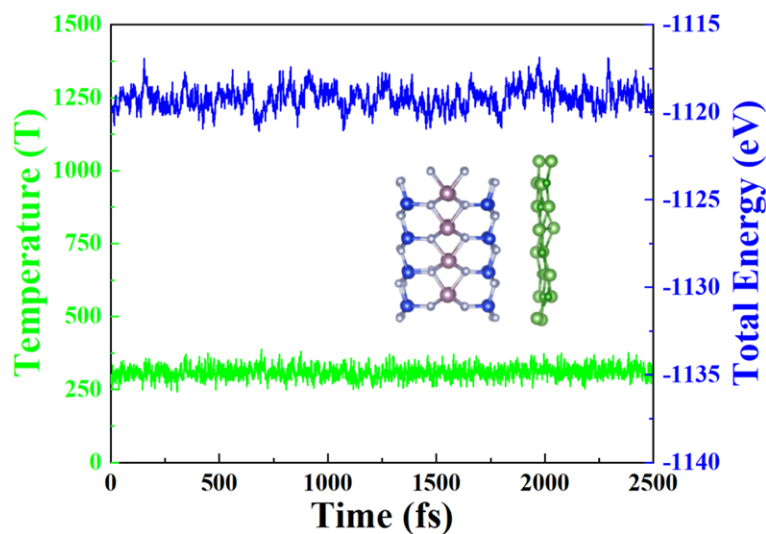


Fig. S2 The AIMD results of A_1 -stacked $\text{BA}/\text{MoSi}_2\text{N}_4$ heterostructure. The evolution

curves of total energy and temperature relative to simulation time are represented by blue and green lines, respectively. The insert shows the final snapshot of the heterostructure after 5 ps.

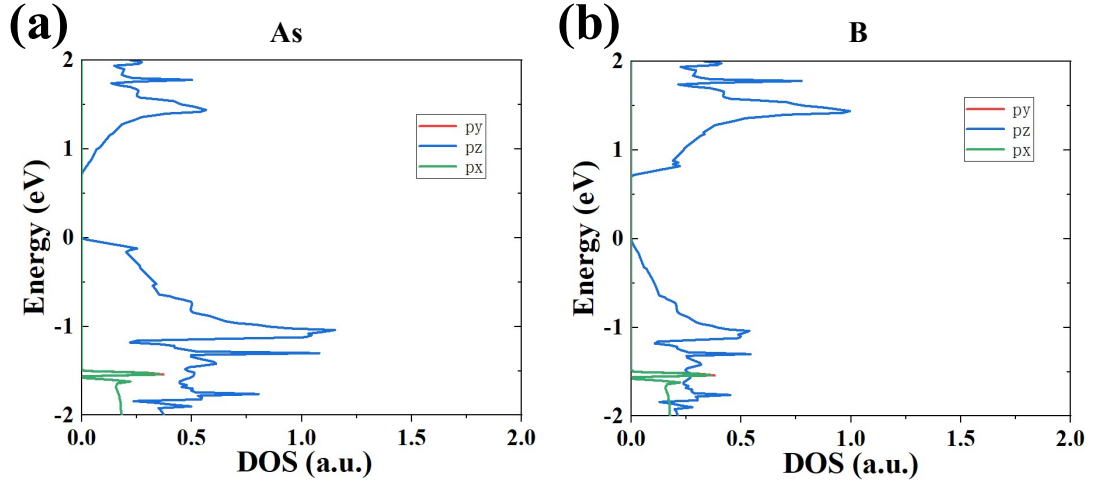


Fig. S3 The density of states of B and As atoms in the $\text{BAs}/\text{MoSi}_2\text{N}_4$ heterostructure.

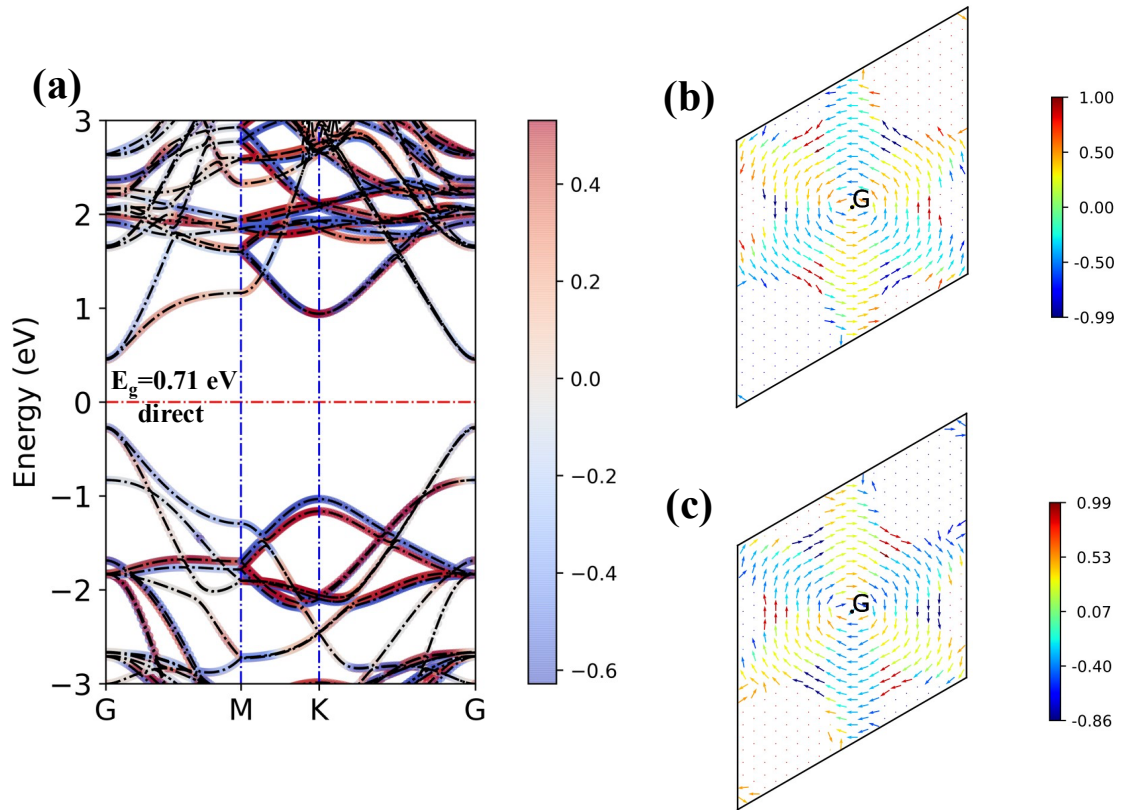


Fig. S4 The band structure of the $\text{BAs}/\text{MoSi}_2\text{N}_4$ heterostructure including SOC. Color represents the weight of S_z in the $\text{BAs}/\text{MoSi}_2\text{N}_4$ heterostructure. The figure on the right shows the spin texture of (b) the highest occupation state and (c) the second highest occupation state near the G point in the Brillouin zone. The arrow represents the in-plane component of spin polarization, and the color represents the out of plane component of spin polarization.

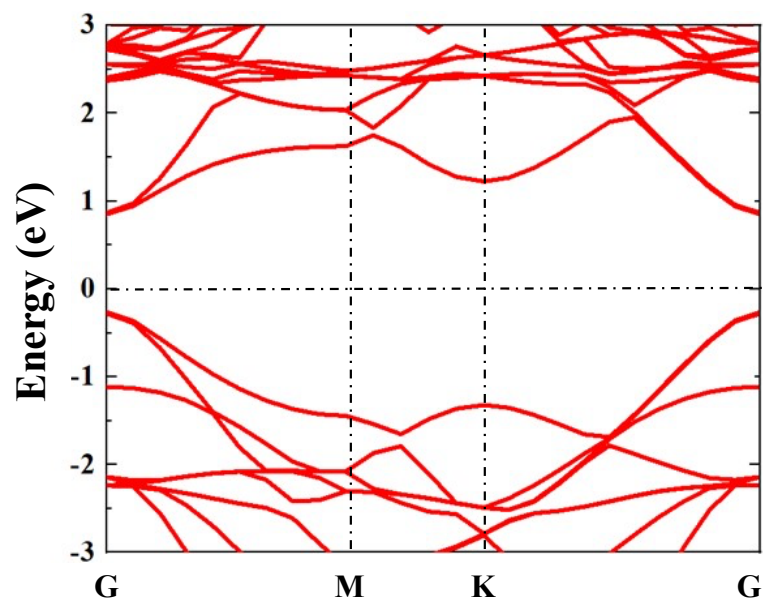


Fig. S5 HSE06 band structure of BA/MoSi₂N₄ heterostructure.

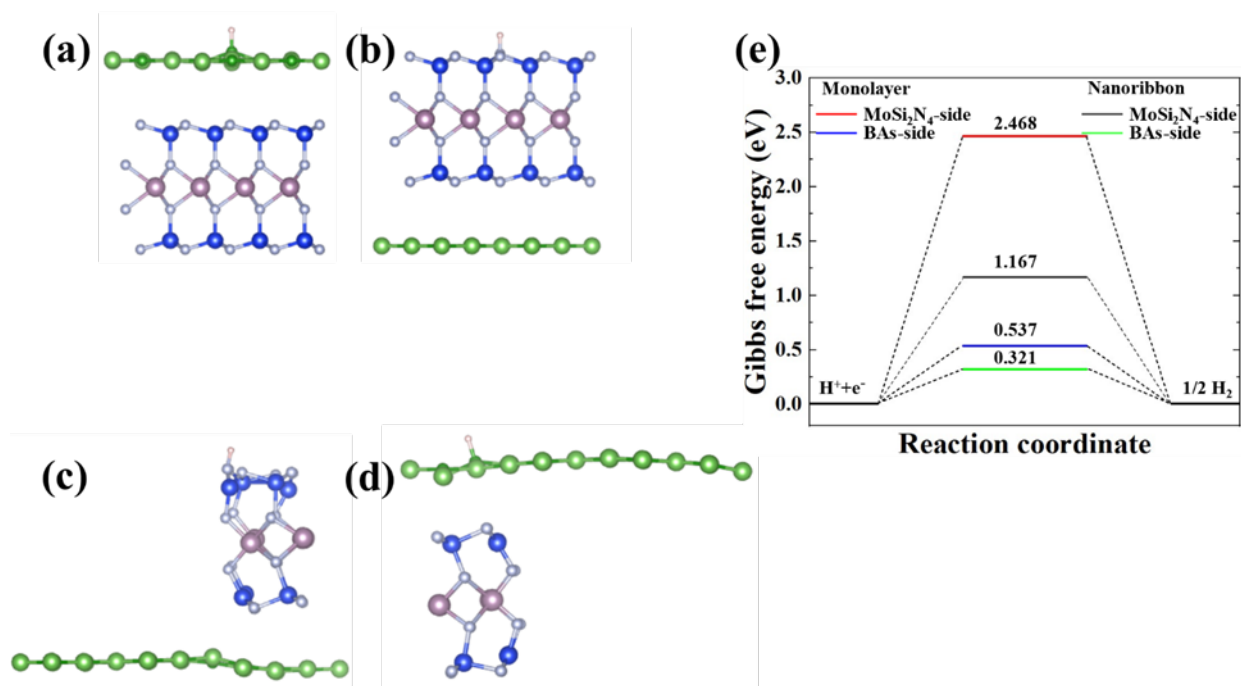


Fig. S6 (a –d) Side view of monolayer and ribbon BA/MoSi₂N₄ heterostructures, with hydrogen atoms adsorbed at the most favorable positions on both sides. (e) Gibbs free energy distribution of HER on both sides of monolayer and ribbon BA/MoSi₂N₄ heterostructures.

Table S1 The lattice constants a and b , equilibrium distance D , bandgap E_g , and total energy E_t of the BAs/MoSi₂N₄ heterostructure under different vacuum layer thicknesses.

Vacuum Layer (Å)	$a = b$ (Å)	D (Å)	E_g (eV)	E_t (eV)
15	5.83	3.9	0.721	-283.9726
20	5.82	3.5	0.716	-283.5109
25	5.82	3.5	0.717	-283.4856